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APPLICATION NO.	F	ILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.
10/684,794	10/14/2003		Jeffrey L. Mackey	108298740US	4238
25096	7590	09/21/2004		EXAMINER	
PERKINS (LP	NGUYEN, HUNG		
PATENT-SE P.O. BOX 12			ART UNIT	PAPER NUMBER	
SEATTLE,	WA 981	11-1247	2851		
				DATE MAILED: 09/21/200	4

Please find below and/or attached an Office communication concerning this application or proceeding.

		Application No.	Applicant(s)			
		10/684,794	MACKEY ET AL.			
	Office Action Summary	Examiner	Art Unit			
		Hung Henry V Nguyen	2851			
Period fo	The MAILING DATE of this communication apports reply	-1	orrespondence address			
THE - Exte after - If the - If NC - Failu Any	MAILING DATE OF THIS COMMUNICATION. Insions of time may be available under the provisions of 37 CFR 1. SIX (6) MONTHS from the mailing date of this communication. In period for reply specified above is less than thirty (30) days, a reply period for reply is specified above, the maximum statutory period ure to reply within the set or extended period for reply will, by statute reply received by the Office later than three months after the mailing led patent term adjustment. See 37 CFR 1.704(b).	136(a). In no event, however, may a reply be tin ly within the statutory minimum of thirty (30) day will apply and will expire SIX (6) MONTHS from e, cause the application to become ABANDONE	nely filed s will be considered timely. the mailing date of this communication. D (35 U.S.C. § 133).			
Status						
1)⊠	Responsive to communication(s) filed on 14 C	October 2003.				
2a) <u></u>	This action is FINAL . 2b)⊠ This	s action is non-final.				
3)[Since this application is in condition for allowance except for formal matters, prosecution as to the merits is closed in accordance with the practice under <i>Ex parte Quayle</i> , 1935 C.D. 11, 453 O.G. 213.					
Disposit	ion of Claims					
5)⊠ 6)⊠ 7)⊠	Claim(s) <u>1-49</u> is/are pending in the application 4a) Of the above claim(s) is/are withdra Claim(s) <u>27-29, 48 and 49</u> is/are allowed. Claim(s) <u>1,2,5,9-13,16-18,30,31,33,34,37-41 and 18 Claim(s) 3,4,6-8,14,15,19-26,32,35,36,42,46 and 18 Claim(s) are subject to restriction and/or</u>	and 43-45 is/are rejected. and 47 is/are objected to.				
Applicat	ion Papers					
10)⊠	The specification is objected to by the Examine The drawing(s) filed on <u>14 October 2003</u> is/are Applicant may not request that any objection to the Replacement drawing sheet(s) including the correct The oath or declaration is objected to by the E	e: a) accepted or b) objected or b) objection is required if the drawing(s) is objection is required if the drawing(s) is objection is required if the drawing(s) is objected or b).	e 37 CFR 1.85(a). jected to. See 37 CFR 1.121(d).			
Priority (under 35 U.S.C. § 119	•				
12)[a)	Acknowledgment is made of a claim for foreign All b) Some * c) None of: 1. Certified copies of the priority documen 2. Certified copies of the priority documen 3. Copies of the certified copies of the priority documen application from the International Burea See the attached detailed Office action for a list	ts have been received. ts have been received in Applicati prity documents have been receive nu (PCT Rule 17.2(a)).	on No ed in this National Stage			
	nt(s) ce of References Cited (PTO-892) ce of Draftsperson's Patent Drawing Review (PTO-948)	4)				
3) 🛛 Infor	mation Disclosure Statement(s) (PTO-1449 or PTO/SB/08 or No(s)/Mail Date 2,4/04 and 10/03.		Patent Application (PTO-152)			

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Art Unit: 2851

DETAILED ACTION

Claim Rejections - 35 USC § 102

1. The following is a quotation of the appropriate paragraphs of 35 U.S.C. 102 that form the basis for the rejections under this section made in this Office action:

A person shall be entitled to a patent unless -

(e) the invention was described in a patent granted on an application for patent by another filed in the United States before the invention thereof by the applicant for patent, or on an international application by another who has fulfilled the requirements of paragraphs (1), (2), and (4) of section 371(c) of this title before the invention thereof by the applicant for patent.

The changes made to 35 U.S.C. 102(e) by the American Inventors Protection Act of 1999 (AIPA) and the Intellectual Property and High Technology Technical Amendments Act of 2002 do not apply when the reference is a U.S. patent resulting directly or indirectly from an international application filed before November 29, 2000. Therefore, the prior art date of the reference is determined under 35 U.S.C. 102(e) prior to the amendment by the AIPA (pre-AIPA 35 U.S.C. 102(e)).

2. Claims 1-2, 5, 9-13, 16-18, 30-31, 33-34, 37-41, and 43-45 are rejected under 35 U.S.C. 102(e) as being anticipated by Sandstrom (U.S.Pat. 6,504,644).

The applicant is reminded that the claimed subject matter to examination will be given their broadest reasonable interpretation consistent with the specification, and limitations appearing in the specification are not be read into the claims. In re Yamamoto, 740 F. 2d 1569, 1571, 222 USPO 934, 936 (Fed.Cir. 1984). With this in mind, the rejection herein will focus on how the terms and relationships thereof in the claims are met by the references. Response to any limitation that is not in the claims or any argument that is irrelevant to or does not relate to any specific claimed language will not be warranted.

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With respect to claims 1, 10-11, 16-18, 30-31, 34, 37-41 and 43-45, Sandstrom discloses an apparatus and corresponding method for controlling characteristics of radiation directed to a microworkpiece and comprising all basic features of the instant claims such as: a workpiece support (605) having a support surface positioned to carry a microlithographic workpiece (see col.14, lines 14-17); a EUV light source positioned to direct a radiation beam along a radiation path toward the workpiece support, the radiation beam having an amplitude distribution, a phase distribution and a polarization distribution; and SML can be regarded as claimed "an adaptive structure" positioned in the radiation path between the source of radiation and the workpiece support, the SLM includes a plurality of individually addressable pixel elements, at least one of these pixel elements includes a layer of electro optical material having a birefringence that varies according to an applied voltage. Each of the plurality of pixel elements is selectively configurable to change form one state to any of a plurality of other states and to modulate both of an amplitude and a phase of radiation that is incident on the pixel element (see col.3, lines 35-67; figures 1-4) and a controller (607) operatively coupled to "the adaptive structure" to direct the elements of the adaptive structure to change from the one state to the one of the plurality of other states.

As to claims 2, Sandstrom teaches the controller (607) is electrically coupled to each of the elements and is configured to apply a variable voltage to each element to independently change a stage of each element from one state to any a plurality of available other states (see figure 1).

As to claim 3, Sandstrom teaches the elements of the adaptive structure (SLM) having a non-time varying transmissibility in each of the states.

With respect to claims 9 and 33, Sandstrom discloses the adaptive structure having a plurality of electrically addressable elements arranged in an array of column and rows (see figure 2).

Allowable Subject Matter

- 3. Claims 3-4, 6-8, 14-15, 19-26, 32, 35-36, 42, 46-47 are objected to as being dependent upon a rejected base claim, but would be allowable if rewritten in independent form including all of the limitations of the base claim and any intervening claims.
- 4. Claims 27-29, 48-49 are allowed.
- 5. The following is a statement of reasons for the indication of allowable subject matter: the prior art either alone or in combination, neither discloses nor makes obvious the combination of an apparatus and corresponding method for controlling characteristic of radiation directed to a microlithographic workpiece, comprising a reticle, an adaptive structure and a controller with particular structures and functions, as recited in the instant claims of the present invention.

Prior Art Made of Record

6. The prior art made of record and not relied upon is considered pertinent to applicant's disclosure.

Johnson (U.S.Pat. 6,498,685); and Shiraishi et al (U.S.Pat. 6,710,854) discloses exposure apparatuses and have been cited for technical background.

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7. Any inquiry concerning this communication or earlier communications from the

examiner should be directed to Hung Henry V Nguyen whose telephone number is 571-272-

2124. The examiner can normally be reached on Monday-Friday (First Friday off).

If attempts to reach the examiner by telephone are unsuccessful, the examiner's

supervisor, Judy Nguyen can be reached on 571-272-2258. The fax phone number for the

organization where this application or proceeding is assigned is 703-872-9306.

Information regarding the status of an application may be obtained from the Patent

Application Information Retrieval (PAIR) system. Status information for published applications

may be obtained from either Private PAIR or Public PAIR. Status information for unpublished

applications is available through Private PAIR only. For more information about the PAIR

system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR

system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

Hung Henry V Nguyen

Primary Examiner
Art Unit 2851

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hvn 9/4/05